



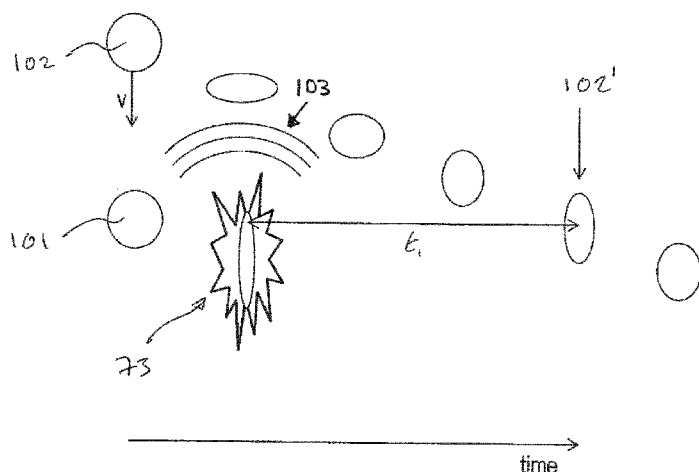
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(54) **Title:** RADIATION SOURCE**Fig. 4**

(57) **Abstract:** A radiation source for generating EUV radiation suitable for use in a lithographic apparatus includes a laser configured to fire laser pulses at a target area to which is supplied a stream of fuel droplets. The fuel droplets may be tin droplets that emit EUV radiation when excited by the laser beam. The EUV radiation is collected by a collector. The tin droplets may be pre-conditioned by a laser pre-pulse before the main laser pulse with the objective of changing the shape of the droplets so that they are in an optimum condition for receiving the main laser pulse. Embodiments of the invention take into account the effect of the vaporization of one fuel droplet on succeeding droplets and allow the timing of the main and/or pre-pulse to be adjusted to take into account any delay in arrival of the subsequent droplet or oscillations in the shape of the subsequent droplet which may be caused by vaporization of the preceding droplet.